

Sep
17

Dry Processing Workshop



Location
TU Vienna

Business
Plasma Technology

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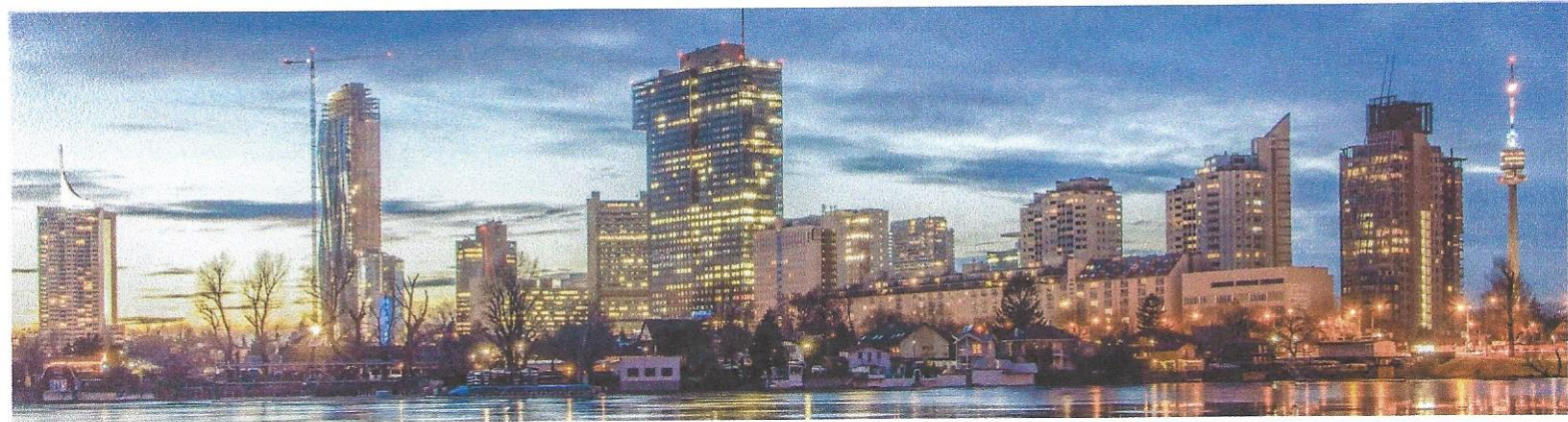
Workshop on Dry Processing for Nanoelectronics & Micromechanics Deposition & Etching, Presented by Oxford Instruments Plasma Technology and TU Vienna. Please see below for confirmed talk titles.

Tuesday 17 September 2019

Wednesday 18 September 2019

Talk Title	Presenter	Organisation
Dry Etching for MEMS Applications	Dr Zhong	Oxford

Talk Title	Presenter	Organisation
Etching of InP & GaAs by Ion beam	Dr	Oxford



Wednesday 18 September 2019

Time	Topic	Speaker
09.30 h – 10.00 h	Etching of InP & GaAs by Ion beam Etching	Dr Sebastien Pochon, Oxford Instruments
10.00 h – 10.30 h	Investigation of the Transition Layer Properties of Plasma Oxidized SiC-SiO ₂ Stacks	Gernot Fleckl, TU Wien - ISAS
10.30 h – 11.00 h	Silicon Etching for Low Loss Integrated Photonics Components	Dr Zhong Ren Oxford Instruments
11.00 h – 11.15 h	COFFEE BREAK	
11.15 - 11.45	Efficient Plasma Cleaning for PECVD	Dr Owain Thomas, Oxford Instruments
11.45 h – 12.15h	ZnO Optoelectronics using Plasma-based Processing	Borislav Hinkov, <i>N. Schrenk</i> FKE und ZMNS, TU Wien
12.15 h – 12.45 h	Diamond Etching – Applications & Challenges	Dr Andrew Newton, Oxford Instruments
12.45 h - 13.45 h	LUNCH BREAK	
13.45 h – 14.15 h	GaN Low Damage Etch by ICP RIE & ALE	Dr Matthew Loveday – Oxford Instruments
14.15 h – 14.45 h	End Point for Ion Beam Applications Including Etching of Magnetic Materials	Dr Sebastien Pochon, Oxford Instruments
14.45 h – 15.15 h	Double-metal Waveguide Fabrication for High Performance THz QCLs	<i>Martin Keinz</i> , u. ZMNS, TU Wien <i>M. Jaidl</i>
15.15 h – 15.30 h	COFFEE BREAK	
15.30 h - 16:00 h	Fabrication of Biomedical Devices: An Overview of Relevant Plasma Processing Technology	Dr Harm Knoops – Oxford Instruments
16.00 h – 16.30 h	Ion Beam Deposition of Nanolayers of VOx & other Materials	Dr Sebastien Pochon, Oxford Instruments
16.30 h	Final Discussion	